CDM: Response form for request for clarification on Approved Methodologies (version 01.1)

Date of Meth Panel meeting:	15-19 October 2012
Title and number of request for clarification	Clarification of the application of equation 2 in the methodology AM_CLA _0239

Summary of the query:

Please use the space below to summarize the request for clarification on the related approved methodologies.

According to the approved CDM methodology AM0092 "Substitution of PFC gases for cleaning Chemical Vapour Deposition (CVD) reactors in the semiconductor industry" (version 1.0.0) the c-C_4F_8 use rate should be calculated as follows:

$$U_{PJ,n,p,t} = \frac{M_{c-C_4F_8,PJ,n,p,t}}{C_{PJ,n,p,t}}$$

Where:

$U_{PJ,n,p,t}$	=	Use rate of c-C_4F_8 cleaning gas during substitute process 'p', with thickness 't' (dimensionless)
$C_{PJ,n,p,t}$	=	Consumption of c-C_4F_8 gas for substitute process 'p', with thickness 't' (g)
$M_{c-C_4F_8,PJ,n,p,t}$	=	Mass outflow of c-C_4F_8 from CVD during substitute process 'p', with thickness 't' (g)
n	=	Number of individual measurements for each substitute process 'p', with thickness 't'

The typographical error in Equation 2 results in a utilization efficiency of zero when the mass outflow of c-C_4F_8 is zero, while in this case the utilization efficiency of c-C_4F_8 should be 100%. This equation is to be compared to equation 11 which is written correctly (for baseline emissions).

In order to correctly calculate the use rate equation 2 should be applied as follows:

$$U_{PJ,n,p,t} = 1 - \frac{M_{c-C_4F_8,PJ,n,p,t}}{C_{PJ,n,p,t}}$$

The clarification is sought on whether the equation 2 should be applied as written in the current version of the methodology or whether the corrected equation should be applied.

Recommendation by the Meth Panel:

Please use the space below to provide amendments /changes (in your expert view, if necessary).

Not applicable.

Answer to authors of the request for clarification by the Meth Panel :

Please use the space below to provide an answer to the authors of the above query

The Meth Panel clarifies that the equation 2 of the approved methodology AM0092 "Substitution of PFC gases for cleaning Chemical Vapour Deposition (CVD) reactors in the semiconductor industry" should read

as follows:

$$U_{PJ,n,p,t} = 1 - \frac{M_{c-C_4F_8,PJ,n,p,t}}{C_{PJ,n,p,t}}$$

The Meth Panel would like to thank the project participants for highlighting this error. The Panel will incorporate this change in the next revision of the methodology.

Signed by the Chair, Mr. Thomas Bernheim
Date: 19/10/2012

Signed by the Vice-Chair, Mr. Hugh Sealy
Date: 19/10/2012

Information to be completed by the secretariat	
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